

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|--|--------------------|---------------------|
| 1 | 1 | ("5997175").PN. | USPAT; US-PGPUB | 2003/08/02 08:15 |
| 2 | 1 | ("5881208").PN. | USPAT; US-PGPUB | 2003/08/02 08:18 |
| 3 | 1 | ("5926742").PN. | USPAT; US-PGPUB | 2003/08/02 08:18 |
| 4 | 430 | ((heating or cooling or annealing or RTP) and gas and (control\$3 with gas with (separately or selectively))) and @ad<20000317) and (wafer or substrate) | USPAT; US-PGPUB | 2003/08/02 08:55 |
| 5 | 329 | ((heating or cooling or annealing or RTP) and gas and (control\$3 with gas with (separately or selectively))) and @ad<20000317) and (wafer or substrate)) and (gas with temperature) | USPAT; US-PGPUB | 2003/08/02 08:28 |
| 6 | 12 | ((heating or cooling or annealing or RTP) and gas and (control\$3 with gas with (separately or selectively))) and @ad<20000317) and (wafer or substrate)) and ((gas with temperature) with (adjust or adjusting)) | USPAT; US-PGPUB | 2003/08/02 08:28 |
| 7 | 1 | ("5819684").PN. | USPAT; US-PGPUB | 2003/08/02 08:51 |
| 8 | 1 | ("6300256").PN. | USPAT; US-PGPUB | 2003/08/02 08:51 |
| 9 | 0 | (controlling with gas with temperature) and (theraml with process) and @ad<20000317 and (wafer or substrate) | USPAT; US-PGPUB | 2003/08/02 08:56 |
| 10 | 269 | (controlling with gas with temperature) and (thermal with process) and @ad<20000317 and (wafer or substrate) | USPAT; US-PGPUB | 2003/08/02 08:56 |